



NOEL Technologies

LPCVD PROCESS

Process	Thickness	Tolerance	Temperature Range
LPCVD Nitride	500A-3KA	±7%	750°C ±10%

WIWNU: Wafer-within-Wafer Non-Uniformity: ±7% @ Range

Wafer Size

mm	Inches
100	4
125	5
150	6
200	8
300	12

Incoming Inspection of Wafers.
SRD, Spin Rinse Dry

Note:

- Upon inspection of wafers, additional cleaning may be required. Customer will be notified for disposition of material to receive the following:
 - SRD, Spin, Rinse Dry
 - SC1/SC2
- Additional processing and or cleaning may result in an additional charge.